

ABSTRACT

SUBSTRATE HOLDING DEVICE, SUBSTRATE POLISHING APPARATUS, AND METHOD OF MANUFACTURING THE SUBSTRATE HOLDING DEVICE

Provided is a substrate holding device used in a substrate polishing apparatus that polishes a substrate using a polishing pad. The substrate holding device includes: a retainer ring configured to hold a peripheral edge of the substrate; and a drive ring fixed to the retainer ring so as to rotate together with the retainer ring. The surface of the retainer ring at the polishing pad side has a convex portion at a position other than an innermost circumference following a shape of the drive ring.

[Representative Drawings] FIG. 2A